LMC:ejv 10/20/09 23-69853-01 E-1861

Filed Via EFS

## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Attorney Docket Number	23-69853-01
Application Number	10/727,062
Filing Date	December 2, 2003
First Named Inventor	John G. DeSteese
Art Unit	1795
Examiner Name	Jeffrey Thomas Barton

## **U.S. PATENT DOCUMENTS**

Copies of U.S. Patent documents do not need to be provided, unless requested by the Patent and Trademark Office. For patents, provide the patent number and the issue date. For published U.S. applications, provide the publication number and the publication date. For unpublished pending patent applications, provide the application number and the filing date and submit a copy.

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EXAMINER /Jeffrey Barton/	DATE CONSIDERED:	01/04/2010
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<sup>\*</sup> Examiner: Initial if reference considered, whether or not in conformance with MPEP 609. Draw line through cite if not in conformance and not considered. Include copy of this form with next communication to applicant.

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